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INTEGRATED CIRCUIT WITH ELECTROSTATIC DISCHARGE PROTECTED POWER SUPPLY

Abstract

An electronic device includes a high-pass filter connected between a first input node and a second input node. A slew rate amplifier is connected coupled to an output of the high-pass filter, and a charge storage node is connected to an output of the slew rate amplifier. A discharge circuit is connected to the charge storage node and has a plurality of discharge paths configured to conduct current between the first and second input nodes in response to a voltage at the charge storage node.

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Background/Summary

CROSS-REFERENCE TO RELATED APPLICATION [0001] This application claims the benefit of and priority to U.S. Provisional Application No. 63/165,867, filed Mar. 25, 2021, which is hereby fully incorporated herein by reference. This Application is a continuation of U.S. Pat. No. 12,294,211, which is hereby fully incorporated herein by reference.

BACKGROUND

[0002] The examples relate to an integrated circuit (IC) with an electrostatic discharge (ESD) protected power supply.

[0003] ESD is the sudden flow of electricity between two objects as electrical charge transfers from one of the objects to the other. For integrated circuit (IC) durability and longevity, ESD protection is included and applied to an IC circuit or IC node(s). In the event of an ESD pulse (strike), ESD protection redirects current to a path, such as away from the IC, that can manage the ESD charge and thereby prevent damage that otherwise could occur were the strike received by an IC signal path. When an ESD strike is not occurring, ideally the ESD protection circuit does not affect IC operation.

[0004] Certain ICs implement structures that are susceptible to ESD events, where for example such structures include pads exposed to the outside of the IC package. Such ICs may include ESD protection, including circuitry that seeks to detect, and is triggered, when an ESD event occurs, where the triggering may be in response to a signal level or a signal slew rate. The HBM model (human body model) defines a range of ESD events differing in the amplitude and the ramp-rate. The slew-rate triggered ESD circuit must be designed to trigger under all conditions to ensure ESD protection. At the same time, some applications have other design considerations that may complicate the goal of properly triggering in response to an ESD event, while avoiding a mistaken triggering during an expected nominal operation of the device. For example, the bootstrap supply in a half-bridge configuration demand fast supply power-up, which typically implies also a small bypass capacitance. However, too fast of a power-up could be potentially triggering if detected by ESD circuitry as a slew-rate exceeding ESD event. Conversely, a larger bypass capacitor naturally limits the maximum supply slew-rate under application conditions, but may be contrary to the desired start-up speed.

[0005] Accordingly, there may be a need or desire to provide ESD protection to such a pad(s), while also responding to other considerations pertaining to the IC. This document provides examples that may improve on certain of the above concepts, as detailed below.

SUMMARY

[0006] In one example, there is an IC, comprising a first rail supply, a second rail supply, an external pad coupled to one of the first rail supply and the second rail supply, and an ESD protection circuit coupled to the external pad. The ESD protection circuit includes a slew rate detector coupled to the external pad, an amplifier coupled to an output of the slew rate detector, a one-shot coupled to an output of the amplifier, and a clamp circuit coupled an output of the one-shot.

[0007] Other aspects and examples are also disclosed and claimed.

Description

BRIEF DESCRIPTION OF THE DRAWINGS

- [0008] FIG. 1 illustrates an electrical diagram of an example ESD protected system.
- [0009] FIG. **2** illustrates a block diagram of the FIG. **1** bootstrap ESD protection circuit.
- [0010] FIG. **3** illustrates a flowchart of an operational method **300** of the FIG. **1** ESD protected system.
- [0011] FIG. **4** illustrates a schematic diagram of a circuit implementation of an example of the FIGS. **1** and **2** bootstrap ESD protection circuit.
- [0012] FIG. **4**A illustrates operation of a portion of the schematic of FIG. **4** that may detect a high slew-rate of an ESD stress to input terminal.
- [0013] FIG. **4**B illustrates operation of a portion of the schematic of FIG. **4** that may boost a dV/dt signal related to an ESD stress to a power rail.
- [0014] FIG. **4**C illustrates operation of a portion of the schematic of FIG. **4** that may operate to clamp a voltage on an input terminal.
- [0015] FIG. **4**D illustrates operation of a portion of the schematic of FIG. **4** that may operate to activate the clamp of FIG. **4**C for a predetermined duration upon the occurrence of an ESD event at an input terminal.
- [0016] FIGS. **5**A and **5**B illustrate timing diagrams of voltages at various nets of the circuit of FIG. **4** in the event of a "medium-to-high" stress (e.g., 2.5 kV ESD stress) to a power terminal.
- [0017] FIGS. **6**A and **6**B illustrate timing diagrams of voltages at various nodes of the circuit of FIG. **4** in the event of a "low" stress (e.g., 40 V ESD stress) to a power terminal.
- [0018] FIGS. 7A and 7B illustrates timing diagrams of current and voltage at various nodes of the circuit of FIG. 4 in the event of a power-up event of the circuit (e.g., with a voltage slew rate of $35V/\mu s$ at a power terminal).

DETAILED DESCRIPTION

[0019] Circuit examples are illustrated and described that include an IC with an ESD protected power supply. The examples are not intended to be exhaustive, as various concepts described in this document may apply to different applications. For example, one application is where an IC includes a power supply rail coupled to a pin exposed outside the IC package, for example for coupling to bypass capacitance, and that pin may introduce an ESD signal into the IC. Further, the typical operation of the IC, for example during startup, may involve a relatively fast change in voltage at the rail. In these instances, selective and accurate ESD protection cells are implemented so that normal startup, with its corresponding fast voltage change, is permitted to occur, without triggering the ESD protection, while in contrast the ESD protection otherwise triggers, and shunts the ESD event, when the rail experiences a voltage increase that is likely to represent an ESD event, as opposed to the normal IC startup or other power supply rail conditions.

[0020] Some baseline ESD protection circuits use large diode structures designed to break down under ESD conditions to reduce damage to a protected circuit. Such diodes may experience snap-back behavior, which can degrade or damage the diode. Such protection circuits may provide one or more of a static trigger, a snap-back behavior, and a dV/dt-triggered active clamp as a feature of ESD protection, and may be inadvertently triggered by transient signals or noise on a protected node.

[0021] Various examples of the disclosure provide active ESD-protection solutions that avoid at least some of the undesirable characteristics of such baseline implementations. Such examples may be beneficially applied to circuit implementations in which switching transients are common and might otherwise trigger baseline ESD protection devices. Various described examples limit an ESD overvoltage on IC power terminals to less than an absolute maximum rating (AMR) of those terminals without triggering ESD suppression during a fast power-up of the device. Some examples further eliminate the need for disabling the ESD suppression circuit during power-up by discriminating between an ESD-related voltage slew rate (dV/dt) and a power-up slew rate on a

protected node. Some examples provide for disabling ESD protection after circuit startup to prevent inadvertent triggering of ESD protection in a noisy circuit environment such as a switching power supply.

[0022] Without limitation, in some examples if a voltage slew rate on a protected node such as a device input terminal exceeds a predetermined value, a signal derived from the protected node voltage is amplified and sampled, for example by charging a charge storage net for a short time, for example tens of nanoseconds. The stored charge is held for a duration commensurate with the duration of an HBM ESD event, for example a few microseconds. One or more discharge transistors is turned on to provide a low-resistance path from the protected node to a current sink of the protected circuit. A relatively small transistor may be turned on to dissipate the charge resulting from a relatively small (low-stress) ESD event, for example tens of volts, while a relatively large transistor may be alternatively or additionally turned on to dissipate the charge resulting from a relatively large (high-stress) ESD event, for example a few kV.

[0023] FIG. 1 illustrates an electrical diagram of an example half-bridge power stage 100, which is ESD protected and is illustrative, but not exhaustive, of an implementation as introduced above. The half-bridge power stage 100 includes a high-side IC 102 and a low-side IC 104, where "highside" and "low-side" are terms in the art typically identifying the relative connection of the highside to a power supply and the low-side relative to ground, and where collectively the sides drive a load. While shown and described in the present example as being implemented by two ICs, the functionality of the high-side IC **102** and the low-side IC **104** may in some examples be provided by a single IC formed on a single common substrate. In FIG. 1, the high-side IC 102 and the lowside IC **104** each include a respective driver **102**DR and **104**DR, and collectively those drivers **102**DR and **104**DR drive a power transistor stage **106**. The power transistor stage **106** includes, for example, a high-side power transistor **108** and a low-side power transistor **110**, each of which may be a separate die or may be formed on a common die. Each of the high-side and low-side power transistors **108** and **110** has a gate connected to a respective output **1020** and **1040** of the high-side IC **102** and the low-side IC **104**. The drain of the high-side power transistor **108** is connected to an input voltage Vin. The source of the high-side power transistor **108** is connected to the drain of the low-side power transistor 110, and that connection provides a power transistor stage output 112, which provides a switching voltage V.sub.SW. The power transistor stage output 112, which may be referred to as a "power output," is connected to a first terminal of a primary winding **114** PW of a transformer **114**, and a second terminal of the primary winding **114**PW is connected to ground. A load **116** is connected between a first terminal and a second terminal of the secondary winding **114**SW of the transformer **114**.

[0024] In an example, the high-side IC **102** and the low-side IC **104** are connected in a half-bridge configuration, wherein startup power to the high-side driver **102**DR is supplied by bootstrapping. As a half-bridge, the switching paths of the high-side IC **102** and the low-side IC **104** are generally complementary, that is, only one conducts at a time so as to alternately enable output by a respective one of the high-side and low-side power transistors **108** and **110**. As a bootstrapped system, a bootstrap capacitor **118** is connected between rails of the high-side IC **102**, namely with a first terminal (e.g., a bottom plate) connected to a second input 122 and a second terminal (e.g., a top plate) connected to a first input **120**, sometimes referred to as a protected node. Each of the first input 120 and second input 122 may be electrically connected to a bond pad (not shown), terminal, or similar I/O structure of a device die. The first terminal of the bootstrap capacitor **118** is also connected to the power transistor stage output 112. In one example as shown, the bootstrap capacitor **118** may be external from the high-side IC **102**, while in an alternative example it may be internally integrated within the high-side IC **102**. In an example, the capacitance of the bootstrap capacitor **118** is relatively low (e.g., 10 nF or less), so as to minimize delay at startup of the overall architecture. The anode of a diode **124** is connected to a first input **126** of the low-side IC **104**, and the cathode of the diode **124** is connected to the second terminal (top plate) of the bootstrap

capacitor **118** and to the first input **120** of the high-side IC **102**. The diode **124** also may be internally integrated within the high-side IC **102**, either without the bootstrap capacitor **118** being integrated, or both of the devices may be so integrated. The first input **126** of the low-side IC **104** is also connected to receive an auxiliary voltage Vaux. Vaux may be the same or a different voltage level as Vin, where in one example both may equal 30 V, although considerably higher voltage levels also may be used, for example particularly with respect to Vin (e.g., up to 650 V or higher). A second input **128** to the low-side IC **104** is connected to a power rail having a relatively low potential (e.g., ground), the source of the low-side power transistor **110**, and to a second terminal of the primary winding **114**PW. A decoupling capacitor **130** is connected between the first input **126** and the second input **128** of the low-side IC **104**. Each of the first input **126** and second input **128** may be electrically connected to a bond pad (not shown), terminal, or similar I/O structure of a device die.

[0025] The half-bridge power stage **100** also includes a bootstrap ESD protection circuit **132**. In an example, the bootstrap ESD protection circuit **132** is integrated as part of the high-side IC **102** and is coupled between the first input 120 and the second input 122, and consequently between the first and second terminal of the bootstrap capacitor **118**. Accordingly, the bootstrap ESD protection circuit **132** can provide a shunt across the bootstrap capacitor **118** and thereby protect the high-side IC **102** from some ESD events. An ESD event to the first input **120** may be tens of volts to kilovolts. An ESD event in a range from tens of volts to a few hundred volts is regarded as a "lowstress" event, an ESD event in a range from a few hundred volts to about a kilovolt is regarded as a "medium-stress" event, and an ESD event greater than a kilovolt is regarded as a "high-stress" event. In an example, the shunt further includes a path to ground through the low-side power transistor **110**, which may act as a current sink. Accordingly, the half-bridge power stage **100** further includes a secondary ESD detection circuit **134**, which may include a dedicated trigger circuit that can enable the low-side power transistor **110** in response to certain ESD events, for example for an ESD surge between the first input **120** and ground or between the power transistor stage output 112 and ground. Accordingly, the secondary ESD detection circuit 134 may be connected to sense a voltage at one or more nodes (not explicitly shown) and, if an ESD pulse is detected at one or more of the monitored nodes, the secondary ESD detection circuit 134 directs an enable signal to the low-side power transistor **110** to form a conductive path between the power transistor stage output **112** and ground in response to the event. Still other ESD protection may be included in other portions of the half-bridge power stage **100** (e.g., within, or coupled to one or more pads, of any IC), but such implementations are beyond the scope of this disclosure. [0026] The typical operation of the half-bridge power stage **100** is now introduced. Generally, the operation toggles between two cycles as may be controlled by respective switching circuits 102SC and 104SC of the high-side IC 102 and the low-side IC 104. Part or all of the switching circuits **102**SC and **104**SC may be implemented (e.g., including pulse width modulators) or controlled either internally or externally relative to the respective IC. Further, each of the switching circuits **102**SC and **104**SC enables the respective driver **102**DR and **104**DR, in alternating respective cycles, to provide a signal to the respective output **1020** and **1040**. For example, in a first cycle, the switching circuit **104**SC enables the driver **104**DR, which is biased between Vaux and ground, while during the first cycle the high-side driver **102**DR is not enabled. In response to being enabled by the switching circuit **104**SC, the driver **104**DR outputs an enabling signal to the output **1040**. The enabling signal is coupled to the gate of the low-side power transistor **110**, thereby causing it to conduct and connecting the power transistor stage output **112** to ground through the source/drain path of the low-side power transistor **110**, causing V.sub.SW to have a ground potential. At the same time, Vaux forward-biases the diode **124** and provides a bootstrap voltage Vbst to the first input **120** of the high-side IC **102**, which charges the bootstrap capacitor **118** at a voltage of Vaux, minus the forward bias voltage drop across the diode **124** and V.sub.SW. The bootstrap voltage Vbst may be referred to herein as a charging voltage. In a second cycle, the switching circuit

102SC enables the driver 102DR, the driver 102DR being biased by the voltage across the bootstrap capacitor 118, plus the voltage Vin (minus the voltage drop across the high-side power transistor 108). Accordingly, the nominal value of Vaux to the driver 102DR is augmented (boosted) by the Vbst voltage that was stored during the first cycle across the bootstrap capacitor 118, thereby providing a robust driving gate voltage to the high-side power transistor 108 greater than its source voltage (at the power transistor stage output 112). The augmented voltage may be referred to a "boost voltage." Accordingly, the high-side power transistor 108 is fully enabled to provide Vin to V.sub.SW, at the power transistor stage output 112. The boost voltage (minus any loss across the high-side power transistor 108) is thereby provided to the transformer 114, which in turn drives the load 116. Thereafter, the above first cycle and second cycle alternate indefinitely, so as to continue to drive the load 116.

[0027] The above-described typical operation occurs so long as no ESD strike occurs. With the addition of the bootstrap capacitor **118**, there is introduced the possibility of an ESD strike to one (e.g., the top plate) or both of the capacitor terminals, to the extent either is exposed outside the IC package. When an ESD strike occurs that charges, for example the top plate of the bootstrap capacitor **118**, the voltage at that location (also shown as the first input **120**) rises, and the bootstrap ESD protection circuit **132** triggers and limits the maximum voltage between the first input **120** and the second input **122**.

[0028] FIG. **2** illustrates a block diagram of the FIG. **1** bootstrap ESD protection circuit **132**. Functionally in an example, the bootstrap ESD protection circuit **132** includes four stages, which as described later may be implemented with separate or shared circuit elements. Each stage is first introduced here, with FIG. 4 later providing a contextual implementation. The bootstrap ESD protection circuit **132** samples a voltage differential, shown in the present FIG. **1** example as Vbst —V.sub.SW. The sampled voltage differential is connected to a slew rate detector **202**, which provides a signal that is responsive to (including representative of) the rate at which the differential input signal changes. The output of the slew rate detector **202** is connected to an amplifier **204**. The amplifier **204** amplifies the slew rate representation signal, so as to more quickly elevate that signal to a level sufficient to change state of one or more circuits (e.g., transistors) to which the amplified signal is provided. The output of the amplifier **204** is connected to a one-shot circuit **206**. If the amplified signal reaches a sufficient level, it triggers the one-shot circuit 206 to output an asserted data signal pulse (e.g., at an output Q) that is high for a duration as established by its circuit components. Lastly, the one-shot circuit **206** output is connected to selectively open or close a switch of clamp circuit **208**, that is, the clamp circuit **208** includes a conductive path configured to be selectively opened and closed, shown schematically in FIG. 2 as a switch 208SW that can discharge to a reference potential, such as ground. The switch **208**SW includes a pole **208**P connected to a signal node at which an ESD strike can occur, such as the bootstrap capacitor 118 second terminal connected to the first input 120 in FIG. 1. Accordingly, if the one-shot circuit 206 outputs an asserted signal, the switch **208**SW closes for the duration of the asserted signal. Once the one-shot circuit **206** output signal is no longer asserted, the switch **208**SW opens. [0029] FIG. **3** illustrates a flowchart of an operational method **300** of the FIG. **1** half-bridge power stage **100**, including the bootstrap ESD protection circuit **132**. A loop including states **304/308/310/312** may operate to protect a circuit when unpowered, as the ESD protection circuit **132** may be powered by an ESD event. The responsive bootstrap ESD protection circuit **132** operation, that is whether an ESD shunt is triggered, depends on a conditional step **304**. The conditional step **304** is conditioned on whether the signal at the bootstrap capacitor **118** is rising too fast compared to a slew rate limit, as evaluated by the FIG. 2 slew rate detector 202. For example, under normal operating conditions of the high and low-side ICs **102** and **104**, Vbst will be expected to ascend at a given rate (e.g., $35 \text{ V/}\mu\text{s}$), Accordingly, the step **304** slew rate conditional limit may be set, for example, at a limit of a multiple (e.g., times two) of the normal expected rate (e.g., 2*35 $V/\mu s=70 V/\mu s$). If Vbst rises at a rate within nominal levels, that is below the step **304** limit (e.g.,

 $70 \text{ V/}\mu\text{s}$), then the method **300** proceeds from step **304** to a step **306**. Conversely, if Vbst rises at a rate above nominal levels, for example at a rate twice or higher than the expected rise rate, then the method **300** proceeds from the step **304** to a step **308**, from where a sequence of successive events implement an ESD shunt of the relatively quickly-ascending Vbst signal.

[0030] Step **306** is reached when the Vbst signal is within nominal levels, that is, not rising at a rate faster than the step **304** limit. Such a condition may be consistent with operation of a protected circuit, such as the half-bridge power stage **100**. In this circumstance it may be desirable to disable the bootstrap ESD protection circuit **132** to prevent being triggered by switching noise on power supply nodes. Thus in a step **305** the slew rate detector **202** may be disabled to prevent further operation of the ESD protection circuit **132** until power is removed from the protected circuit, at which point the step **304** becomes operative again. In response to disabling the slew rate detector **202**, the bootstrap ESD protection circuit **132** presents a relatively high impedance, in parallel to the bootstrap capacitor **118**. Accordingly, negligible or no current flows through the bootstrap ESD protection circuit **132**, and the operation of the bootstrap capacitor **118** is undisturbed by the ESD protection. Further, the bootstrap ESD protection circuit **132** does not provide a low resistance conductive path to shunt any charge during the step **306**, so the high-side IC **102** and the low-side IC **104** operate according to nominal parameters and functions and without material impact from the bootstrap ESD protection circuit **132**.

[0031] If the bootstrap capacitor voltage is determined to be rising faster than the slew rate conditional limit at the step **304**, then the method **300** advances to step **308**, and the steps **310** and **312** following it. The steps **306**, **310**, and **312** represent the operations of the FIG. **2** amplifier **204**, one-shot **206**, and clamp circuit **208**, respectively, which occur when Vbst rises too rapidly per the step **304** condition. Specifically, when such a signal rise occurs, the signal rise is attributed to an ESD strike, and the steps **308**, **310**, and **312** collectively combine to shunt the fast-rising Vbst signal. After operating to shunt the ESD current, the method **300** returns to the decision step **304** to continue protecting the half-bridge power stage **100** circuit. Additional possible implementation details in connection with each of these steps are further discussed in connection with FIG. **4**, below.

[0032] FIG. **4** illustrates a schematic of a circuit **400** that may implement the bootstrap ESD protection circuit **132** of FIGS. **1** and **2** according to some examples. The circuit **400** is only by example and only certain components are shown so as to simplify the illustration, while other components and connections may be included, added, or substituted by one skilled in the art given the teachings of the disclosure. Generally, circuit **400** components are connected between the first input **120** and the second input **122** of the high-side IC **102**, the first and second inputs **120**, **122** having voltages Vbst and V.sub.SW, respectively. In the following discussion, portions of the circuit **400** are shown in isolation for clarity.

[0033] FIG. 4A illustrates a first capacitor 402 (C.sub.1) and a first resistor 406 (R.sub.1) as a non-limiting example of the slew rate detector 202. The first capacitor 402 is connected between the first input 120 and a first node 404, also designated net_nt and sometimes referred to as a sample node. The first resistor 406 is connected between the first node 404 and the second input 122. Thus the first capacitor 402 and first resistor 406 are an example of a high-pass filter that provides a time-dependent signal to the node 404 in response to a change of Vbst. In an example, the capacitance of the first capacitor 402 and the resistance of the first resistor 406 are together selected so that the RC time constant τ , which is the product of R.sub.1 and C.sub.1, provides a predetermined time period that distinguishes between a relatively fast slew rate that is characteristic of an ESD event and a relatively slow slew rate characteristic of normal operation, such as powering up or operating the circuit 400. Operation of the components of FIG. 4A is described more fully below.

[0034] FIG. **4**B illustrates components that in a non-limiting example may implement operation of the amplifier **204**. A first PMOS transistor **408** (MP**1**) has its source connected to the first input **120**

and its gate connected to a second node **410**, also sometimes referred to as node_Pad-pf. The gate is also connected through a second resistor **407** (R.sub.2) to the first input **120**. The drain of the first PMOS transistor **408** is connected to the first node **404** (net_nt). The first node **404** is also connected to a drain of a first NMOS transistor **412** (MN**8**), which has its source connected to the second input **122**. The gate of the first NMOS transistor **412** is connected through a third resistor **414** (R.sub.3) to a third node **416** (net_nh) and through a second capacitor **418** (C.sub.2) to the second input **122**. The third node **416**, sometimes described as a hold node, is also connected to the source of a second NMOS transistor **420** (MN**4**), which has its drain connected to the first input **120** and its gate connected to the first node **404**. The first node **404** is further connected to the gate of a third NMOS transistor **422** (MN**7**). The source of the third NMOS transistor **422** is connected to the second input **122**, and its drain is connected to a source of a fourth NMOS transistor **424** (MN**6**). The gate of the fourth NMOS transistor **424** is connected to the third node **416**, and the drain of the fourth NMOS transistor **424** is connected to the second node **410**. Operation of the components of FIG. **4B** is described more fully below.

[0035] FIG. 4C illustrates components that in a non-limiting example may implement operation of the clamp circuit 208. A gate of a fifth NMOS transistor 426 (MN1) is connected to the third node 416 (net_nh). A drain of the fifth NMOS transistor 426 is connected to the first input 120, and a source of the fifth NMOS transistor 426 is connected to the second input 122. A source of a second PMOS transistor 428 (MP0) is connected to the first input 120, and a gate of the second PMOS transistor 428 is connected through a fourth resistor 430 (R.sub.4) to the first input 120, and to the drain of a sixth NMOS transistor 432 (MN2). A source of the sixth NMOS transistor 432 is connected to the second input 122. A drain of the second PMOS transistor 428 is connected at a fourth node 446 (net_ng) to a first terminal of a fifth resistor 434 (R.sub.5). A second terminal of the fifth transistor 434 is connected to the second input 122. A gate of a seventh NMOS transistor 436 (MN3) receives the signal from the fourth node 446. The drain of the seventh NMOS transistor 436 is connected to the first input 120 and its source is connected to the second input 122. Operation of the components of FIG. 4C is described more fully below.

[0036] FIG. 4D illustrates components that in a non-limiting example may implement operation of the one-shot **206** in cooperation with the clamp circuit **208**. A third capacitor **438** (C.sub.3) and a sixth resistor **440** (R.sub.6) are connected in parallel between the third node **416** and the second input **122**, forming an RC circuit. When charged by the third node **416** (net_nh), the capacitor **438** may discharge at a rate determined by the respective resistance and capacitance of the third capacitor **438** and the sixth resistor **440**. Thus the third capacitor **438** can maintain a voltage on the net_nh for a period of time determined by the time constant of the RC circuit to enable the NMOS transistors **426** and **432** (FIG. **4**C). Operation of the components of FIG. **4**D is described more fully below.

[0037] Concluding the structure of FIG. **4**, in an example, an optional slew rate disabling circuit **442** also may be included, so as to override the function of the FIG. **2** slew rate detector **202**. For example, the ESD protection may be used during material handling prior to start-up. So once start-up is complete and the half-bridge power stage **100** is providing a stable power supply (e.g., to the FIG. **1** load **116**), a control signal CTRL may be asserted to the slew rate disabling circuit **442**, thereby disabling the bootstrap ESD protection circuit **132**. In an example, the slew rate disabling circuit **442** is implemented by an eighth NMOS transistor **444** (MN**9**), with its drain connected to the first node **404**, its source connected to the second input **122**, and its gate connected to receive the CTRL signal. Accordingly, when the CTRL signal is asserted (active high), the eighth NMOS transistor **444** source/drain path shorts together the terminals of the first resistor **406**, thereby preventing it from charging and likewise preventing a triggering of the remaining functionality, including clamping functionality, of the bootstrap ESD protection circuit **132**. [0038] The operation of the protection circuit **132** as exemplified by the circuit **400** is now further described, with different portions described to generally align with, and further illustrate an

example of, the earlier-described discussions of FIG. **2** and FIG. **4**. The following narrative may overlap and augment the previous discussions.

[0039] Referring to FIG. 4A, the first capacitor 402 and the first resistor 406 act as a high-pass filter of the Vbst at the first input 120, with a frequency breakpoint at ω .sub.B=1/ τ . If the slew rate of a voltage transient on Vbst is relatively slow compared to ω .sub.B (e.g., low-frequency), then the transient is filtered and the voltage at the first node 404 (net_nt) remains relatively low; as a result, that voltage, coupled as shown in FIGS. 4 and 4B to the gates of the second and third NMOS transistors 420 and 422, will not exceed the turn-on voltage of the second NMOS transistor 420 and the third NMOS transistor 422, so paths that may be enabled by those transistors in the circuit 400 remain inactive. On the contrary, if the slew rate of the voltage at the first input 120 rises relatively quickly, e.g. has sufficient spectral energy at frequencies greater than ω .sub.B, then the voltage at the first node 404 may exceed the turn-on voltage of the second NMOS transistor 420 and the third NMOS transistor 422 and thereby initiate additional operation of the circuit 400. The first capacitor 402 and the first resistor 406 thereby implement the FIG. 2 slew rate detector 202, and the second NMOS transistor 420 and the third NMOS transistor 422 may be regarded as cooperating with the first capacitor 402 and the first resistor 406 to implement the slew rate detector 202.

[0040] The operation of the circuit portion of FIG. 4B may be further illustrated by reference to the circuit paths 1-8. Initially as shown by circuit path 1, the gates of the second and third NMOS transistors 420 and 422 receive a voltage (from the slew rate detector 202) at the first node 404 (net_nt). If the received voltage is sufficiently enabling, the second NMOS transistor 420 turns on, raising the voltage at the third node 416 to Vbst, thereby turning on the fourth NMOS transistor 424. Thus the slew rate detector 202 operates as a separate trigger to initiate operation of the amplifier 204. With both the third and fourth NMOS transistors 422 and 424 on, the voltage at the second node 410 (node_pad-pf) is pulled to V.sub.SW through the second resistor 407 as shown by circuit path 2. The value of the second resistor 407 may be selected in view of expected ESD events to limit Vbst to a value that does not exceed an AMR of the gate of the first PMOS transistor 408. The first PMOS transistor 408 is thus turned on as shown by circuit path 3. With the first PMOS transistor 408 on (circuit path 4), the first node 404 (net_nt) is pulled to Vbst by the (protected node) first input 120 and the second NMOS transistor 420 is maintained in an on-state for the duration of the time during which the ESD pulse on the first input 120 remains above the turned-on voltage of the second NMOS transistor 40 (circuit path 5).

[0041] Also with the second NMOS transistor **420** turned on, the first input **120** is conductively connected to the third node **416** (net_nh), and the second capacitor **418** is charged through the resistor **414** (circuit path 6). After a time determined by the resistance of the third resistor **414** and the capacitance of the second capacitor **418**, net_nf between the resistor **414** and the second capacitor 418 reaches the turn-on voltage of the first NMOS transistor 412 and enables the first NMOS transistor **412** (circuit path 7). The first NMOS transistor **412** then pulls the first node **404** (net_nt) to V.sub.SW (circuit path 8), thereby stopping the current flow through the second, third, and fourth NMOS transistors **420**, **422**, and **424**. An effect of these events is that the initial signal at the node **404** (net_nt) sourced by the slew rate detector (e.g., as implemented by the FIG. **4**A first capacitor **402** and the first resistor **406**) is amplified using the voltage Vbst, the amplified signal provided on the third node **416** (net_nh). Thus the components of FIG. **4**B cooperate to implement the FIG. **2** amplifier **204**, which renders the selective ESD shunt more sensitive and selective, so as to ensure ESD protective triggering and clamping at the desired detected rates of change of Vbst. [0042] The net nh/nf includes charging nodes for the second capacitor **418** and the third capacitor **438**. Thus this net provides internal charge storage for the circuit **400**. While the conducting second NMOS transistor **420** provides in part the above-described amplifier functionality, the current through circuit path **6** (FIG. **4**B) charges the second capacitor **418**, and a voltage from the second NMOS transistor **420** source (at the third node **416**) is also coupled to and enables the sixth NMOS

transistor **432** (see also FIG. **4**C). Additionally, the third node **416** voltage charges the third capacitor **438**, with the charge rate also potentially affected by the resistance of the sixth resistor **440** (see also FIG. **4**D). In an example, the third capacitor **438** has a larger capacitance than the second capacitor **418**, for example by a factor of **10**, so that the third capacitor **438** will remain charged for a longer relative period, for example at least as long as the duration of an ESD event. In this regard, the stored charge across the third capacitor **438** implements the FIG. **2** one-shot **206**, for the duration that such charge remains sufficient to enable the FIG. **2** clamp circuit **208**. Accordingly, for the one-shot **206** duration, it maintains an enabling voltage at the third node **416**. In part, the conductive path and resulting one-shot voltage also disables the prior amplification from the devices forming the amplifier **204**, namely, the second capacitor **418** is charged, which enables the first NMOS transistor **412** (MN**8**) and thereby provides a discharge path to ground, for example which will then couple to ground current that is conducted through the second NMOS transistor **420**.

[0043] The one-shot maintained voltage at the third node **416** enables one or more discharge paths between the first input **120** and the second input **122**. In the FIG. **4** example, a first discharge path is through the fifth NMOS transistor **426**, which has a source/drain path directly connected between those nodes. Accordingly, the fifth NMOS transistor **426**, as a singularly enabled transistor, provides an adequate and relatively fast triggered shunt discharge for relatively low human body model (HBM) ESD stress. Further, a second and amplified discharge path is provided, while slightly delayed (e.g., a few nanoseconds) but with larger shunt capacity, by the combination of the second PMOS transistor 428 and the sixth and seventh NMOS transistors 432 and 436. Particularly, the third node **416** voltage enables the sixth NMOS transistor **432** and as a result the source/drain path of the sixth NMOS transistor 432 connects the gate of the second PMOS transistor 428 to the second input 122, thereby enabling the second PMOS transistor 428. As a result, the source/drain path of the second PMOS transistor **428** connects the first input **120** to the gate of the seventh NMOS transistor **436**, which also is directly connected between the first input **120** and the second input **122**. The NMOS transistor **436** may be a larger transistor, for example having a greater gate width than the NMOS transistor **426**, allowing the NMOS transistor **436** to dissipate a greater current from the first input **120** without damage. In some examples the NMOS transistor **436** may have a gate width at least ten times larger than the gate width of the NMOS transistor 426, and in some implementations may have a gate width 50 times or greater than the NMOS transistor **426** gate width. Accordingly, the seventh NMOS transistor **436** provides an adequate shunt discharge for larger HBM ESD stress.

[0044] FIGS. 5A and 5B illustrate simulated voltages over time at various nodes in the circuit **400** according to one example. FIG. 5A includes two traces, V_pad at the first input 120 and V_nt at the first node **404**. FIG. **5**B includes five traces, V_ng at the first input **120**, V_nh at the third node **416**, V_pad-np at the gate of the second PMOS transistor **428**, V_nf at the gate of the first NMOS transistor **412** and V_pad-pf at the second circuit node **410**. The voltage traces reflect the simulated condition of the first input **120** (or pad) receiving a 2.5 kV HBM ESD event at t=0. This ESD event is an example of a medium/high stress event. Trace V_nt reflects the voltage at the first node **404**, or the boosted trigger for the circuit **400**. This node experiences a 6 V pulse that has a duration of about 40 ns. Trace V_nf shows the voltage on the charge storage net_nh that includes the second and third capacitors **418** (C.sub.2) and **438** (C.sub.3). This voltage trace is also the gate voltage of the low stress path between the inputs **120** and **122** through the fifth NMOS transistor **426**, and the gate voltage of the medium/high stress discharge trigger sixth NMOS transistor **432**. [0045] As seen in FIG. 5B for the conditions of the medium/high stress operation, trace V_nh shows the voltage on the net_nh that provides the gate voltage to the low-stress fifth NMOS transistor **426** and the medium/high stress trigger sixth NMOS transistor **432**. This trace is seen to initially reach a voltage of about 4.5 V for the duration of the boosted trigger signal, and then gradually decreases from about 4 V to about 3.5 V over the next 700 ns. Trace V_ng shows the

voltage on the net_ng that provides the gate voltage to the seventh NMOS transistor **436** in response to the voltage on the net_nh. The net_ng initially increases to about 5.5 V, sufficient to turn on the sixth NMOS transistor 432, and decreases with an approximately exponential decrease to about 1.5 V with a time constant related to the capacitance on the charge storage net nh. This results in the sixth NMOS transistor **432** initially conducting between the inputs **120** and **122** during the medium/high stress event, after which conduction through the low stress fifth NMOS transistor **426** is sufficient to completely discharge the ESD event. As a result of the combination of the discharge paths, the voltage at the first input **120** is limited to about 13 V under these conditions, well below a typically achievable AMR of the half-bridge power stage **100**. [0046] FIGS. **6**A and **6**B illustrate modelled voltages over time at the same nodes as shown in FIGS. 5A and 5B, but for the simulated condition of the first input 120 (or pad) receiving a 40 V HBM ESD event at t=0. This ESD event is an example of a low stress event. Traces corresponding to the seven nets are again shown, V_pad, V_nt, V_pad-np, V_nh, V_ng, V_nf and V_pad-pf. Trace V_pad shows that the pad (first input **120**) voltage is limited to about 6.2 V. Trace V_nt (boosted trigger signal) experiences a 4.5 V spike with a duration at its peak of about 10 ns. Trace V_pad-np (the second PMOS transistor 428 gate node) has a maximum of about 3.5 V and decreases over a broader time range than the pad. The net_nh voltage (trace V_nh) remains at about 2 V over the simulated time frame, while the net_ng voltage (trace V_ng) remains at about 1.8 V until 200 ns, and then decreases exponentially after the trace V_nf rises high enough to turn on the first NMOS transistor **412**, which experiences an exponential increase to about 2 V at 300 ns and a gradual decline thereafter. Trace V_pad-pf qualitatively resembles trace V_pad, with a maximum of about 2.2 V. As a result of these interactions of the circuit **400** components, the pad voltage is limited to well below the AMR of the components of the half-bridge power stage 100. [0047] Finally, FIGS. 7A and 7B illustrate modelled electrical parameters over time at the relevant subset of the nodes shown in FIGS. 5A and 5B, but for the simulated condition of a startup condition of the half-bridge power stage **100** with a 35 V/µs power-up slew rate at the first input **120**. The startup may be, for example, at the beginning of one phase of one cycle of an indefinitely repeating number of cycles of operation of the half-bridge power stage 100. FIG. 7A shows a trace I_pad with a vertical scale in μ A, showing an initial current at the first input **120** of about 500 μ A, and decreasing to about 150 µA by about 850 ns. This period may be representative of one period of operation of the high side of the half-bridge power stage **100** operating at about 588 kHz. Trace V_nt shows that the boosted trigger signal at the node **404** has a maximum voltage of about 450 mV at 50 ns after circuit start-up. The trace V_nh (low-stress gate voltage) reaches a maximum voltage of about 460 mV at 850 ns, while the trace V_ng (medium/high stress gate voltage) initially peaks at about 100 mV and exponentially decays to the end of the 850 ns phase. These data show that in under such conditions (e.g., in the absence of an ESD event of at least 40 V), neither the low-stress discharge path nor the medium/high stress discharge paths operates, allowing the half-

[0048] The illustrated examples provide an IC with and ESD protected bootstrapped power supply. An example is shown as a half bridge power converter, while inventive aspects may be applied to other architectures. Examples may implement the ESD protection at startup or thereafter, or a startup protection may be disabled once a sufficiently stable operation is established. Further, these described examples may provide one or more of various benefits over prior ESD devices. For example, examples may provide protection to either high or low ESD spikes, in the event of a fast slew rate signal, while not triggering or introducing inrush currents during nominal power-up events. Examples also may be implemented without a static voltage level ESD trigger, at least as far as the bootstrap signal detection is concerned. Further, examples also may tolerate decoupling capacitance up to a certain limit, thereby avoiding the possible delay or operational slowdown from a higher capacitive implementation. Still further, examples may be implemented without external control at power-up and also can minimize so-called latch-up, that is, ESD triggering either at

bridge power stage **100** to operate normally.

undesired times or under nominal conditions. As still another benefit, various inventive aspects can be implemented in a variety of configurations. Different levels of configuration details have been presented, and the inventive scope may include still others as contemplated or may be determined by one skilled in the art from the teachings of this document. Accordingly, additional modifications are possible in the described examples, and others are possible, within the scope of the following claims.

Claims

- **1**. An electronic device, comprising: a high-pass filter coupled between a first input node and a second input node; a slew rate amplifier coupled to an output of the high-pass filter; a charge storage node coupled to an output of the slew rate amplifier; and a discharge circuit coupled to the charge storage node and having a plurality of discharge paths configured to conduct current between the first and second input nodes in response to a voltage at the charge storage node.
- **2**. The electronic device of claim 1, wherein the high-pass filter includes a resistor and a capacitor connected in series between the first and second input nodes.
- **3.** The electronic device of claim 1, further comprising a second resistor and a second capacitor connected in parallel between the charge storage node and the second input node.
- **4.** The electronic device of claim 1, wherein a first discharge path is operable to conduct between the first and second input nodes with a first maximum current, and a second discharge path is operable to conduct between the first and second input nodes with a greater second maximum current.
- **5.** The electronic device of claim 1, wherein a first discharge path includes a first MOS transistor having a first gate width and a second discharge path includes a second MOS transistor having a greater second gate width.
- **6.** The electronic device of claim 5, wherein the second gate width is at least ten times the first gate width.
- **7**. The electronic device of claim 5, wherein the second gate width is at least fifty times the first gate width.
- **8**. An electrical system, comprising: a first switching transistor connected between a first voltage rail and a transformer node, and a second switching transistor connected between the transformer node and a second voltage rail; a driver circuit coupled to the first switching transistor and having first and second voltage inputs; a protection circuit connected between the first and second voltage inputs, the protection circuit including: a high-pass filter coupled between the first and second voltage inputs; an amplifier coupled to an output of the high-pass filter; a charge storage circuit coupled to an output of the amplifier; and a discharge circuit coupled to an output of the charge storage circuit and having a plurality of discharge paths configured to conduct current between the first and second voltage inputs in response to a voltage produced by the charge storage circuit.
- **9.** The electrical system of claim 8, further comprising a bootstrap capacitor connected between the first and second voltage inputs.
- **10**. The electrical system of claim 8, wherein the high-pass filter includes a resistor and a capacitor coupled in series between the first and second voltage inputs.
- **11**. The electrical system of claim 8, wherein the first and second switching transistors are formed on a same semiconductor die.
- **12**. The electrical system of claim 8, wherein the driver circuit is a first driver circuit formed on or over a substrate, and further comprising a second driver circuit formed on or over the substrate and connected to the second switching transistor.
- **13**. The electrical system of claim 8 and further comprising a transformer connected to the transformer node and configured to provide a load current to a load.
- **14**. A method of forming an electronic device, comprising: forming a high-pass filter connected

between a first input node and a second input node; forming a slew rate amplifier connected to an output of the high-pass filter; forming a charge storage circuit connected to an output of the slew rate amplifier and having a charge storage node; and forming a discharge circuit connected to the charge storage node and having a plurality of discharge paths configured to conduct current between the first and second input nodes in response to a voltage at the charge storage node.

- **15**. The method of claim 14, wherein the high-pass filter includes a resistor and a capacitor connected series between the first and second input nodes.
- **16**. The method of claim 14, wherein the charge storage circuit includes second resistor and a second capacitor connected in parallel between the charge storage node and the second input node.
- **17**. The method of claim 14, wherein a first one of the plurality of discharge paths is operable to conduct between the first and second input nodes with a first maximum current, and a second one of the plurality of discharge paths is operable to conduct between the first and second input nodes with a greater second maximum current.
- **18**. The method of claim 14, wherein a first discharge path includes a first MOS transistor having a first gate width and a second discharge path includes a second MOS transistor having a greater second gate width.
- **19**. The method of claim 18, wherein the second gate width is at least ten times the first gate width.
- **20**. The method of claim 18, wherein the second gate width is at least fifty times the first gate width.